

2010 年度業績 —節原 裕一

学術論文・解説記事

1. Y. Setsuhara, K. Cho, M. Shiratani, M. Sekine, M. Hori, X-ray photoelectron spectroscopy for analysis of plasma-polymer interactions in Ar plasmas sustained via RF inductive coupling with low-inductance antenna units, *Thin Solid Films*, 518, 3555-3560, 2010
2. Y. Setsuhara, K. Cho, K. Takenaka, M. Shiratani, M. Sekine, M. Hori, E. Ikenaga, S. Zaima, Low-damage surface modification of polymethylmethacrylate with argon oxygen mixture plasmas driven by multiple low-inductance antenna units, *Thin Solid Films*, 518, 3561-3565, 2010
3. K. Cho, K. Takenaka, Y. Setsuhara, M. Shiratani, M. Sekine, M. Hori, E. Ikenaga, H. Kondo, O. Nakatsuka and S. Zaima, Hard X-ray Photoelectron Spectroscopy Analysis for Organic Inorganic Hybrid Materials Formation, *Ceramic Transactions*, 219, 183-188, 2010
4. K. Takenaka, Y. Nakajima, Y. Setsuhara, H. Abe and K. Nogi, Plasma-Enhanced Nanoparticles-Beam Deposition For High-Rate Formation of Nanocomposite Films, *Ceramic Transactions*, 219, 293-297, 2010
5. K. Takenaka, Y. Setsuhara, K. Cho, M. Shiratani, M. Sekine and M. Hori, Combinatorial Analysis of Plasma-Surface Interactions of Polyethyleneterephthalate with X-ray Photoelectron Spectroscopy, *Japanese Journal of Applied Physics*, 49, 08JA02-1-4, 2010
6. Y. Setsuhara, K. Cho, K. Takenaka, M. Shiratani, M. Sekine and M. Hori, Advanced Research and Development for Plasma Processing of Polymers with Combinatorial Plasma-Process Analyzer, *Thin Solid Films*, 518, 6320-6324, 2010
7. Y. Setsuhara, K. Cho, M. Shiratani, M. Sekine and M. Hori, X-Ray photoelectron spectroscopy analysis of plasma polymer interactions for development of low-damage plasma processing of soft materials, *Thin Solid Films*, 518, 6492-6495, 2010
8. Y. Setsuhara, K. Cho, K. Takenaka, M. Shiratani, M. Sekine, and M. Hori, Low-Damage Plasma Processing of Polymers for Development of Organic-Inorganic Flexible Devices, *Surface and Coating Technology*, 205, S355-S359, 2010
9. K. S. Shin, Y. S. Choi, I. S. Choi, Y. Setsuhara, J. G. Han, Nano-crystalline silicon thin films grown by the inductively coupled plasma assisted CFUBM at low temperature, *Surface and Coating Technology*, 205, S227-S230, 2010
10. Y. Setsuhara, Plasma Technologies for Large-Area, Low-Damage and Reactive Processes Using Multiple Low-Inductance Antenna Modules, *J. Plasma Fusion Res.*, 87, 24-33, 2010

受賞

1. 節原 裕一, (独) 日本学術振興会 プラズマ材料科学第 153 委員会 第 12 回プラズマ材料科学賞 (奨励部門) , 2010 年 7 月 23 日